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Edition 3.1 2021-06 CONSOLIDATED VERSION

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Semiconductor devices – Discrete devices – Part 8: Field-effect transistors

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Semiconductor devices – Discrete devices – Part 8: Field-effect transistors



CONTENTS

– 2 –

FΟ	REW	ORD		6
1	Scope			
2	Norm	native re	eferences	8
3	Terms and definitions			9
	3.1	Types	of field-effect transistors	9
	3.2		al terms	
		3.2.1	Physical regions (of a field-effect transistor)	10
		3.2.2	Functional regions	11
	3.3	Terms	related to ratings and characteristics	12
	3.4	Conve	ntional used terms	17
4	Lette	r symbo	ols	17
	4.1	Gener	al	17
	4.2 Additional general subscripts		17	
	4.3	List of	letter symbols	17
		4.3.1	Voltage	17
		4.3.2	Currents	18
		4.3.3	Power dissipation	19
		4.3.4	Small-signal parameters	19
		4.3.5	Other parameters	20
		4.3.6	Matched-pair field-effect transistors	21
		4.3.7	Inverse diodes integrated in MOSFETs for N-channel	
5	Esse	ntial rat	tings and characteristics	22
· ·	al	22		
		5.1.1	Device categories	22
		5.1.2	Multiple-gate devices	22
		5.1.3	Handling precautions	22
	5.2	Ratings (limiting values)		
		5.2.1	Temperatures	
		5.2.2	Power dissipation (Ptot)	
		5.2.3	Safe operating area (SOA) for MOSFET only	
		5.2.4	Voltages and currents	
	5.3		cteristics	
		5.3.1	Characteristics for low-frequency amplifier	
		5.3.2	Characteristics for high-frequency amplifier	
		5.3.3	Characteristics for high and low power switching and chopper	
		5.3.4	Characteristics for low-level amplifier	
		5.3.5	Characteristics for voltage-controlled resistor	32
		5.3.6	Specific characteristics of matched-pair field-effect transistors for low-frequency differential	
6	Meas	suring n	nethods	34
	6.1	Gener	al	34
	6.2	Verific	ation of ratings (limiting values)	34
		6.2.1	Voltages and currents	34
		6.2.2	Safe operating area	
		6.2.3	Avalanche energy	45

	6.3	Method	ds of measurement	47	
		6.3.1	Breakdown voltage, drain to source (V(BR)DS*)	47	
		6.3.2	Gate-source off-state voltage (VGS(off)) (type A and B), gate source threshold voltage (VGS(th)) (type C)	48	
		6.3.3	Drain leakage current (d.c.) (IDS*)(type C), Drain cut-off current (d.c.) (IDSX) (type A and B)	49	
		6.3.4	Gate cut-off current (IGS*)(type A), Gate-leakage current (IGS*)(type B and C)	49	
		6.3.5	(Static) drain-source on-state resistance $(r_{DS(on)})$ or drain-source on-state voltage $(V_{DS(on)})$	50	
		6.3.6	Switching times ($t_{d(on)}$, t_{r} , $t_{d(off)}$, and t_{f})	52	
		6.3.7	Turn-on power dissipation (P_{on}) , turn-on energy (per pulse) (E_{on})		
		6.3.8	Turn-off power dissipation ($P_{\rm Off}$), turn-off energy (per pulse) ($E_{\rm Off}$)	54	
		6.3.9	Gate charges (QG, QGD, QGS(th), QGS(pI))	54	
		6.3.10	Common source short-circuit input capacitance (Ciss)	55	
		6.3.11	Common source short-circuit output capacitance (Coss)	56	
		6.3.12	Common source short-circuit reverse transfer capacitance (C _{rss})	57	
		6.3.13	Internal gate resistance (rg)	58	
		6.3.14	MOSFET forward recovery time (t_{fr}) and MOSFET forward recovered charge (Q_f)	59	
		6.3.15	Drain-source reverse voltage (✓ DSR V _{SD})	64	
			Small-signal short-circuit output conductance (type A, B and C) ($g_{ extsf{OSS}}$)		
		6.3.17	Small-signal short-circuit forward transconductance (types A, B and C)	67	
		6.3.18	Noise (types A, B and C) (F, Vn)	69	
			On-state drain-source resistance (under small-signal conditions) (rds(on))		
		6.3.20	Channel-case transient thermal impedance $(Z_{th(j-c)})$ and thermal resistance $(R_{th(i-c)})$ of a field-effect transistor		
7	Acce	ptance	and reliabilityand reliability		
	7.1	Genera	al requirements	73	
	7.2	Acceptance-defining characteristics			
	7.3	•	ance and reliability tests		
		7.3.1	High-temperature blocking (HTRB)		
		7.3.2	High-temperature gate bias		
		7.3.3	Intermittent operating life (load cycles)		
	7.4	Type to	ests and routine tests	75	
		7.4.1	Type tests	75	
		7.4.2	Routine tests		
Bib	oliogra	phy		77	
Fig	gure 1	– Basic	waveforms to specify the gate charges	14	
Fiç	jure 2	Integr	al times for the turn-on energy $E_{ m ON}$ and turn-off energy $E_{ m Off}$	16	
			hing times		
_			it diagram for testing of drain-source voltage		
			it diagram for testing of gate-source voltage		
			it diagram for testing of gate-drain voltage		
L16	juie /	- Dasic	circuit for the testing of drain current	31	

Figure 21 — Circuit diagram for drain leakage (or off-state) current or drain cut-off current measurement	Figure 8 – Circuit diagram for testing of peak drain current	38
Figure 11 — Circuit diagram for verifying FBSOA	Figure 9 – Basic circuit for the testing of reverse drain current of MOSFETs	38
Figure 12 – Circuit diagram for verifying RBSOA	Figure 10 – Basic circuit for the testing of peak reverse drain current of MOSFETs	39
Figure 13 – Test waveforms for verifying RBSOA	Figure 11 – Circuit diagram for verifying FBSOA	40
Figure 14 — Circuit for testing safe operating pulse duration at load short circuit	Figure 12 – Circuit diagram for verifying RBSOA	41
Figure 15 – Waveforms of gate-source voltage VGS, drain current /D and voltage VDS during load short circuit condition SCSOA	Figure 13 – Test waveforms for verifying RBSOA	42
4 Figure 16 – Circuit for the inductive avalanche switching	Figure 14 – Circuit for testing safe operating pulse duration at load short circuit	43
Figure 17 – Waveforms of ID, VDS and VGS during unclamped inductive switching		43
Figure 18 – Waveforms of I _D , V _{DS} and V _{GS} for the non-repetitive avalanche switching	Figure 16 – Circuit for the inductive avalanche switching	45
Figure 19 – Circuit diagrams for the measurement drain-source breakdown voltage	Figure 17 – Waveforms of $I_{ extsf{D}},\ V_{ extsf{DS}}$ and $V_{ extsf{GS}}$ during unclamped inductive switching	45
Figure 20 – Circuit diagram for measurement of gate-source off-state voltage and gate-source threshold voltage	Figure 18 – Waveforms of $I_{ m D},~V_{ m DS}$ and $V_{ m GS}$ for the non-repetitive avalanche switching	46
Figure 21 – Circuit diagram for drain leakage (or off-state) current or drain cut-off current measurement. 4 Figure 22 – Circuit diagram for measuring of gate cut-off current or gate leakage current. 5 Figure 23 – Basic circuit of measurement for on-state resistance. 5 Figure 24 – On-state resistance. 5 Figure 25 – Circuit diagram for switching time. 5 Figure 26 – Schematic switching waveforms and times. 5 Figure 27 – Circuit for determining the turn-on and turn-off power dissipation and/or energy. 5 Figure 28 – Circuit diagrams for the measurement gate charges. 5 Figure 29 – Basic for the measurement of short-circuit input capacitance. 5 Figure 30 – Basic circuit for measurement of short-circuit output capacitance (Coss). 5 Figure 31 – Circuit for measurement of internal gate resistance. 5 Figure 32 – Circuit diagram for MOSFET forward recovery time and recovered charge (Method 1). 6 Figure 34 – Current waveform through MOSFET (Method 1). 6 Figure 35 – Circuit diagram for MOSFET forward recovery time and recovered charge (Method 2). 6 Figure 36 – Current waveform through MOSFET (Method 2). 6 Figure 37 – Circuit diagram for the measurement of drain-source reverse voltage. 6 Figure 37 – Circuit diagram for the measurement of the output conductance goss (method 1: null method). 6 Figure 39 – Basic circuit for the measurement of the output conductance goss (method 2: two-voltmeter method). 6 Figure 40 – Circuit for the measurement of short-circuit forward transconductance goss (method 2: two-voltmeter method). 6 Figure 41 – Circuit for the measurement of forward transconductance goss (method 2: two-voltmeter method).	Figure 19 – Circuit diagrams for the measurement drain-source breakdown voltage	47
Figure 22 — Circuit diagram for measuring of gate cut-off current or gate leakage current		48
Figure 23 – Basic circuit of measurement for on-state resistance		49
Figure 24 – On-state resistance		50
Figure 25 — Circuit diagram for switching time	Figure 23 – Basic circuit of measurement for on-state resistance	51
Figure 26 – Schematic switching waveforms and times	Figure 24 – On-state resistance	51
Figure 27 – Circuit for determining the turn-on and turn-off power dissipation and/or energy	Figure 25 – Circuit diagram for switching time	52
Figure 28 – Circuit diagrams for the measurement gate charges	Figure 26 – Schematic switching waveforms and times	52
Figure 29 – Basic for the measurement of short-circuit input capacitance		53
Figure 30 – Basic circuit for measurement of short-circuit output capacitance $(C_{\rm OSS})$	Figure 28 – Circuit diagrams for the measurement gate charges	55
Figure 31 – Circuit for measurement of reverse transfer capacitance $C_{\rm FSS}$	Figure 29 – Basic for the measurement of short-circuit input capacitance	56
Figure 32 – Circuit for measurement of internal gate resistance	, , , , , , , , , , , , , , , , , , , ,	
Figure 33 – Circuit diagram for MOSFET forward recovery time and recovered charge (Method 1)	Figure 31 – Circuit for measurement of reverse transfer capacitance $ extit{ extit{C}}_{ exttt{rss}}$	58
(Method 1)6Figure 34 - Current waveform through MOSFET (Method 1)6Figure 35 - Circuit diagram for MOSFET forward recovery time and recovered charge (Method 2)6Figure 36 - Current waveform through MOSFET (Method 2)6Figure 37 - Circuit diagram for the measurement of drain-source reverse voltage6Figure 38 - Basic circuit for the measurement of the output conductance g_{OSS} (method 1: null method)6Figure 39 - Basic circuit for the measurement of the output conductance g_{OSS} (method 2: two-voltmeter method)6Figure 40 - Circuit for the measurement of short-circuit forward transconductance g_{fS} (Method 1: Null method)6Figure 41 - Circuit for the measurement of forward transconductance g_{fS} (method 2: two-voltmeter method)6	Figure 32 – Circuit for measurement of internal gate resistance	59
Figure 35 – Circuit diagram for MOSFET forward recovery time and recovered charge (Method 2)		60
(Method 2)	Figure 34 – Current waveform through MOSFET (Method 1)	61
Figure 37 – Circuit diagram for the measurement of drain-source reverse voltage		62
Figure 38 – Basic circuit for the measurement of the output conductance $g_{\rm OSS}$ (method 1: null method)	Figure 36 – Current waveform through MOSFET (Method 2)	63
1: null method)	Figure 37 – Circuit diagram for the measurement of drain-source reverse voltage	64
2: two-voltmeter method)		65
(Method 1: Null method)		66
two-voltmeter method)6	(Method 1: Null method)	67
Figure 42 – Block diagram for the measurement of equivalent input noise voltage6		68
g	Figure 42 – Block diagram for the measurement of equivalent input noise voltage	69

IEC 60747-8:2010+AMD1:2021 CSV	
Figure 43 – Circuit for the measurement of equivalent input noise voltage	69
Figure 44 – Circuit diagram for the measurement of on-state drain-source resistance	70
Figure 45 – Circuit diagram	71
Figure 46 – Circuit for high-temperature blockings	74
Figure 47 – Circuit for high-temperature gate bias	74
Figure 48 – Circuit for intermittent operating life	75
Table 1 – Terms for MOSFET in this standard document and the conventional used terms for the inverse diode integrated in the MOSFETs for N-channel	17
Table 2 – Acceptance defining characteristics	34
Table 3 – Acceptance-defining characteristics for endurance and reliability tests	73
Table 4 – Minimum type and routine tests for FETs when applicable	76

- 6 - IEC 60747-8:2010+AMD1:2021 CSV © IEC 2021

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SEMICONDUCTOR DEVICES – DISCRETE DEVICES –

Part 8: Field-effect transistors

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This consolidated version of the official IEC Standard and its amendment has been prepared for user convenience.

IEC 60747-8 edition 3.1 contains the third edition (2010-12) [documents 47E/398/FDIS and 47E/406/RVD] and its amendment 1 (2021-06) [documents 47E/726/CDV and 47E/744/RVC].

In this Redline version, a vertical line in the margin shows where the technical content is modified by amendment 1. Additions are in green text, deletions are in strikethrough red text. A separate Final version with all changes accepted is available in this publication.

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-7 -

International Standard IEC 60747-8 has been prepared by subcommittee 47E: Discrete semiconductor devices, of IEC technical committee 47: Semiconductor devices.

This third edition constitutes a technical revision.

The main changes with respect to the previous edition are listed below.

- a) "Clause 3 Classification" was moved and added to Clause 1.
- b) "Clause 4 Terminology and letter symbols" was divided into "Clause 3 Terms and definitions" and "Clause 4 Letter symbols" was amended with additions and deletions.
- c) Clause 5, 6 and 7 were amended with necessary additions and deletions.

This publication has been drafted in accordance with the ISO/IEC Directives, Part 2.

This Part 8 should be used in conjunction with IEC 60747-1:2006.

A list of all the parts in the IEC 60747 series, under the general title Semiconductor devices – Discrete devices, can be found on the IEC website.

Future standards in this series will carry the new general title as cited above. Titles of existing standards in this series will be updated at the time of the next edition.

The committee has decided that the contents of the base publication and its amendment will remain unchanged until the stability date indicated on the IEC web site under "http://webstore.iec.ch" in the data related to the specific publication. At this date, the publication will be

- reconfirmed,
- withdrawn,
- · replaced by a revised edition, or
- amended.

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-8-

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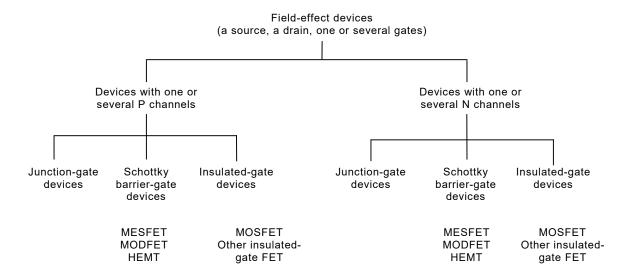
Part 8: Field-effect transistors

1 Scope

This part of IEC 60747 gives standards for the following categories of field-effect transistors:

- type A: junction-gate type;
- type B: insulated-gate depletion (normally on) type;
- type C: insulated-gate enhancement (normally off) type.

Since a field-effect transistor may have one or several gates, the classification shown below results:



NOTE 1 Schottky barrier-gate and insulated gate devices include depletion type devices and enhancement type devices.

NOTE 2 MOSFETs for some applications may not have inverse diode characteristics in the data sheet. Special circuit element structures to eliminate body diode are under development for such applications. MOSFET applications such as motor control equipment need to specify the inverse diode characteristics in the MOSFET to use the inverse diode as a free wheeling diode.

NOTE 3 The graphical symbol only for type C is used in this standard. The standard equally applies for P-channel and for type A and B devices.

2 Normative references

The following referenced documents are indispensable for the application of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

IEC 61340 (all parts), Electrostatics

IEC 60747-1:2006, Semiconductor devices - Part 1: General

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IEC 60747-7:2000, Semiconductor devices – Part 7: Bipolar transistors

IEC 60749-23:2004, Semiconductor devices – Mechanical and climatic test methods – Part 23: High temperature operating life

IEC 60749-34, Semiconductor devices – Mechanical and climatic test methods – Part 34: Power cycling



IEC 60747-8

Edition 3.1 2021-06 CONSOLIDATED VERSION

FINAL VERSION

Semiconductor devices – Discrete devices – Part 8: Field-effect transistors



CONTENTS

– 2 –

FC	REW	ORD		6
1	Scop	oe		8
2	Norn	native r	eferences	8
3	Terms and definitions			
	3.1	Types	of field-effect transistors	g
	3.2		al terms	
	0	3.2.1	Physical regions (of a field-effect transistor)	
		3.2.2	Functional regions	
	3.3	Terms	related to ratings and characteristics	
	3.4		entional used terms	
4	Lette	er symb	ols	17
	4.1	Gener	al	17
	4.2 Additional general subscripts		17	
	4.3	List of	letter symbols	17
		4.3.1	Voltage	17
		4.3.2	Currents	18
		4.3.3	Power dissipation	18
		4.3.4	Small-signal parameters	18
		4.3.5	Other parameters	20
		4.3.6	Matched-pair field-effect transistors	21
		4.3.7	Inverse diodes integrated in MOSFETs for N-channel	21
5	Esse	ential ra	tings and characteristics	22
	5.1	Gener	al	22
		5.1.1	Device categories	22
		5.1.2	Multiple-gate devices	22
		5.1.3	Handling precautions	22
	5.2	Ratings (limiting values)		22
		5.2.1	Temperatures	22
		5.2.2	Power dissipation (Ptot)	22
		5.2.3	Safe operating area (SOA) for MOSFET only	22
		5.2.4	Voltages and currents	23
	5.3	Chara	cteristics	23
		5.3.1	Characteristics for low-frequency amplifier	23
		5.3.2	Characteristics for high-frequency amplifier	
		5.3.3	Characteristics for high and low power switching and chopper	
		5.3.4	Characteristics for low-level amplifier	
		5.3.5	Characteristics for voltage-controlled resistor	32
		5.3.6	Specific characteristics of matched-pair field-effect transistors for low-frequency differential	33
6	Mea	suring n	nethods	34
	6.1	Gener	al	34
	6.2	Verific	cation of ratings (limiting values)	34
		6.2.1	Voltages and currents	34
		6.2.2	Safe operating area	40
		6.2.3	Avalanche energy	44

	6.3	Methods of measurement		
		6.3.1	Breakdown voltage, drain to source (V(BR)DS*)	46
		6.3.2	Gate-source off-state voltage ($V_{GS(off)}$) (type A and B), gate source threshold voltage ($V_{GS(th)}$) (type C)	
		6.3.3	Drain leakage current (d.c.) (IDS*)(type C), Drain cut-off current (d.c.) (IDSX) (type A and B)	
		6.3.4	Gate cut-off current (IGS*)(type A), Gate-leakage current (IGS*)(type B and C)	
		6.3.5	(Static) drain-source on-state resistance $(r_{DS(on)})$ or drain-source on-state voltage $(V_{DS(on)})$	49
		6.3.6	Switching times ($t_{d(on)}$, t_{r} , $t_{d(off)}$, and t_{f})	
		6.3.7	Turn-on power dissipation (P_{on}) , turn-on energy (per pulse) (E_{on})	
		6.3.8	Turn-off power dissipation (P_{off}), turn-off energy (per pulse) (E_{off})	
		6.3.9	Gate charges (QG, QGD, QGS(th), QGS(pl))	
		6.3.10	Common source short-circuit input capacitance (C_{iss})	
			Common source short-circuit output capacitance (Coss)	
			Common source short-circuit reverse transfer capacitance (C_{rss})	
		6.3.13	Internal gate resistance (r _g)	57
			MOSFET forward recovery time ($t_{ m fr}$) and MOSFET forward recovered charge ($Q_{ m f}$)	
		6.3.15	Drain-source reverse voltage (V _{SD})	62
			Small-signal short-circuit output conductance (type A, B and C) (goss)	
		6.3.17	Small-signal short-circuit forward transconductance (types A, B and C)	
		6.3.18	Noise (types A, B and C) (F, Vn)	67
		6.3.19	On-state drain-source resistance (under small-signal conditions) (rds(on))	68
		6.3.20	Channel-case transient thermal impedance $(Z_{th(j-c)})$ and thermal resistance $(R_{th(j-c)})$ of a field-effect transistor	69
7	Acce	ptance	and reliability	
	7.1	Genera	al requirements	71
	7.2	Accept	ance-defining characteristics	71
	7.3		ance and reliability tests	
		7.3.1	High-temperature blocking (HTRB)	
		7.3.2	High-temperature gate bias	
		7.3.3	Intermittent operating life (load cycles)	
	7.4	Type to	ests and routine tests	
		7.4.1	Type tests	
		7.4.2	Routine tests	
Bib	oliogra	phy		
- :-		D : -		4.4
			waveforms to specify the gate charges	
Fig	jure 2	Integr	al times for the turn-on energy E_{on} and turn-off energy E_{off}	16
Fig	gure 3	Switch	ning times	21
Fig	gure 4	– Circui	t diagram for testing of drain-source voltage	35
Fiç	gure 5	– Circui	t diagram for testing of gate-source voltage	35
			t diagram for testing of gate-drain voltage	
			circuit for the testing of drain current	
. 16	jui G 1	Dasic	on our for the testing of drain our out	01

Figure 8 – Circuit diagram for testing of peak drain current	38
Figure 9 – Basic circuit for the testing of reverse drain current of MOSFETs	38
Figure 10 – Basic circuit for the testing of peak reverse drain current of MOSFETs	39
Figure 11 – Circuit diagram for verifying FBSOA	40
Figure 12 – Circuit diagram for verifying RBSOA	41
Figure 13 – Test waveforms for verifying RBSOA	41
Figure 14 – Circuit for testing safe operating pulse duration at load short circuit	42
Figure 15 – Waveforms of gate-source voltage <i>V</i> _{GS} , drain current <i>I</i> _D and voltage <i>V</i> _I during load short circuit condition SCSOA	os 43
Figure 16 – Circuit for the inductive avalanche switching	44
Figure 17 – Waveforms of I_D , V_{DS} and V_{GS} during unclamped inductive switching	44
Figure 18 – Waveforms of I_{D} , V_{DS} and V_{GS} for the non-repetitive avalanche switch	ing45
Figure 19 – Circuit diagrams for the measurement drain-source breakdown voltage .	46
Figure 20 – Circuit diagram for measurement of gate-source off-state voltage and gasource threshold voltage	
Figure 21 – Circuit diagram for drain leakage (or off-state) current or drain cut-off current measurement	48
Figure 22 – Circuit diagram for measuring of gate cut-off current or gate leakage current	49
Figure 23 – Basic circuit of measurement for on-state resistance	50
Figure 24 – On-state resistance	50
Figure 25 – Circuit diagram for switching time	51
Figure 26 – Schematic switching waveforms and times	51
Figure 27 – Circuit for determining the turn-on and turn-off power dissipation and/or	
energy Figure 28 – Circuit diagrams for the measurement gate charges	
Figure 29 – Basic for the measurement of short-circuit input capacitance	
Figure 30 – Basic circuit for measurement of short-circuit output capacitance (C_{OSS})	
Figure 31 – Circuit for measurement of reverse transfer capacitance C_{rss}	
Figure 32 – Circuit for measurement of internal gate resistance	
Figure 33 – Circuit diagram for MOSFET forward recovery time and recovered charg (Method 1)	
Figure 34 – Current waveform through MOSFET (Method 1)	59
Figure 35 – Circuit diagram for MOSFET forward recovery time and recovered charg (Method 2)	
Figure 36 – Current waveform through MOSFET (Method 2)	61
Figure 37 – Circuit diagram for the measurement of drain-source reverse voltage	62
Figure 38 – Basic circuit for the measurement of the output conductance $g_{\rm OSS}$ (meth 1: null method)	od
Figure 39 – Basic circuit for the measurement of the output conductance $g_{\rm OSS}$ (meth 2: two-voltmeter method)	
Figure 40 – Circuit for the measurement of short-circuit forward transconductance g_1 (Method 1: Null method)	
Figure 41 – Circuit for the measurement of forward transconductance g_{fS} (method 2 two-voltmeter method)	
Figure 42 – Block diagram for the measurement of equivalent input noise voltage	67

IEC 60747-8:2010+AMD1:2021 CSV	
Figure 43 – Circuit for the measurement of equivalent input noise voltage	67
Figure 44 – Circuit diagram for the measurement of on-state drain-source resistance	68
Figure 45 – Circuit diagram	69
Figure 46 – Circuit for high-temperature blockings	72
Figure 47 – Circuit for high-temperature gate bias	72
Figure 48 – Circuit for intermittent operating life	73
Table 1 – Terms for MOSFET in this document and the conventional used terms for the inverse diode integrated in the MOSFETs for N-channel	17
Table 2 – Acceptance defining characteristics	34
Table 3 – Acceptance-defining characteristics for endurance and reliability tests	71
Table 4 – Minimum type and routine tests for FETs when applicable	74

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SEMICONDUCTOR DEVICES – DISCRETE DEVICES –

Part 8: Field-effect transistors

FOREWORD

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This consolidated version of the official IEC Standard and its amendment has been prepared for user convenience.

IEC 60747-8 edition 3.1 contains the third edition (2010-12) [documents 47E/398/FDIS and 47E/406/RVD] and its amendment 1 (2021-06) [documents 47E/726/CDV and 47E/744/RVC].

This Final version does not show where the technical content is modified by amendment 1. A separate Redline version with all changes highlighted is available in this publication.

- 6 **-**

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-7 -

International Standard IEC 60747-8 has been prepared by subcommittee 47E: Discrete semiconductor devices, of IEC technical committee 47: Semiconductor devices.

This third edition constitutes a technical revision.

The main changes with respect to the previous edition are listed below.

- a) "Clause 3 Classification" was moved and added to Clause 1.
- b) "Clause 4 Terminology and letter symbols" was divided into "Clause 3 Terms and definitions" and "Clause 4 Letter symbols" was amended with additions and deletions.
- c) Clause 5, 6 and 7 were amended with necessary additions and deletions.

This publication has been drafted in accordance with the ISO/IEC Directives, Part 2.

This Part 8 should be used in conjunction with IEC 60747-1:2006.

A list of all the parts in the IEC 60747 series, under the general title Semiconductor devices – Discrete devices, can be found on the IEC website.

Future standards in this series will carry the new general title as cited above. Titles of existing standards in this series will be updated at the time of the next edition.

The committee has decided that the contents of the base publication and its amendment will remain unchanged until the stability date indicated on the IEC web site under "http://webstore.iec.ch" in the data related to the specific publication. At this date, the publication will be

- reconfirmed,
- withdrawn,
- replaced by a revised edition, or
- amended.

-8-

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SEMICONDUCTOR DEVICES – DISCRETE DEVICES –

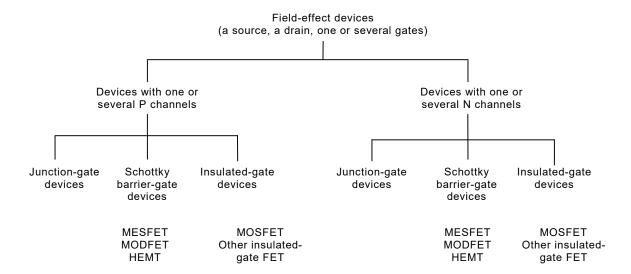
Part 8: Field-effect transistors

1 Scope

This part of IEC 60747 gives standards for the following categories of field-effect transistors:

- type A: junction-gate type;
- type B: insulated-gate depletion (normally on) type;
- type C: insulated-gate enhancement (normally off) type.

Since a field-effect transistor may have one or several gates, the classification shown below results:



NOTE 1 Schottky barrier-gate and insulated gate devices include depletion type devices and enhancement type devices.

NOTE 2 MOSFETs for some applications may not have inverse diode characteristics in the data sheet. Special circuit element structures to eliminate body diode are under development for such applications. MOSFET applications such as motor control equipment need to specify the inverse diode characteristics in the MOSFET to use the inverse diode as a free wheeling diode.

NOTE 3 The graphical symbol only for type C is used in this standard. The standard equally applies for P-channel and for type A and B devices.

2 Normative references

The following referenced documents are indispensable for the application of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

IEC 61340 (all parts), Electrostatics

IEC 60747-1:2006, Semiconductor devices - Part 1: General

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IEC 60747-7:2000, Semiconductor devices – Part 7: Bipolar transistors

IEC 60749-23:2004, Semiconductor devices – Mechanical and climatic test methods – Part 23: High temperature operating life

IEC 60749-34, Semiconductor devices – Mechanical and climatic test methods – Part 34: Power cycling